

## O3.304 Plasma assisted synthesis of carbon nanowalls

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See the full abstract here:

<http://ocs.ciemat.es/EPS2019ABS/pdf/O3.304.pdf>

Plasmas can be used for the fabrication of novel materials. The interest in novel, often carbonaceous materials with large effective surfaces, high conductivity, stability, is growing due to the downsizing of electrical devices and the demand for low-cost new materials. In particular this work will focus on the analysis of a low temperature plasma (RF -discharge) used for the production of carbon nanowalls (CNWs).

The resulting nanowalls (CNWs) demonstrate interesting characteristics, and have a potential for variety of applications. In our case, we tested electrochemical devices, transistors and biosensors. This work with CNWs is a part of the research on carbon based microelectronic parts of biosensors.

Besides the material analysis of nanowalls (graphene 2D structures) the plasma parameters were analysed and connected with the material analysis in order to understand and control better the plasma processes itself. For example, the self-bias voltage is correlated with OES and XPS and NEXAFS analysis of CNW produced in ethylene or acetylene/hydrogen gas mixtures.

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